L Number		Search Text Mizuochi-Masaki.in.	DB USPAT; US-EGPUB;	Time stamp 2903/04/24 09:30
-	74	Fukushima-Yoshimasa.in.	EPC; JPC USEAT; US-1GEUE;	2003/04/24 09:30
-	21	Fustushima Woshimasa in. and chamber	EEC; JPO USEAT; US-IGEUE;	1003/04/24 10:34
-	ţ	Innoe-Mitsurt.in.	EEC; JPC USEAT; US-EGEUE; EEC; JPC	2003/04/24 09:31
-	595:	050[492.1.ppls. 250/492.2 ccls. 15 492.3.ppls. 050/442.11.pcls.	USEAT; US-IGEUB; EES; JPC	2003/04/24 09:32
-	1634	2:1 492.1.pdls. 150/492.2.pdl4. .5 4 0.3.ppls. 170/442.11.pdl4.) and charlies	USEAT, US-EGPUB; EED; JPO	2000,104 124 09:3€
-	87)	1250-430.1.dcls. [50]440.2.ccls. .5-440.3.schs. [50]440.11 [ccls.] and	USFAT; US-PGPUE; EEL; SPC	2003 104 124 09:33
-		250 400.1.cols. 0.0 402.2 cols. 250/480.4.cols. 0.0 (441.11.cols.) and recess33 process same (ring annuls3))	ULIAT; UL-EGEUE; EEI; JEC	1000,04 24 09:34
-	2	<pre>106 44.11.c:ls. co(4432.2.ccls. 250497.3 inds. If (441.11.ccls.) and chambers and (250/441.11.ccls. 250492.3.ccls. 150/492.3.ccls. 250441.11.ccls. and table) and 2 in 481.1.ccls. 250/492.3.ccls. 250/40.3.ccls. 20/441.11.ccls.) and 2 page 213 crocyell same aring annuls?)))</pre>	UHEAT; UH-PGPUH; EEU; JPC	2001,104 124 09:36
-	÷	Furushin: Yoshimara and (Groove ring)	USEAT; US-EGPUE; EET; JPC	2000,04 024 10:35
-	3	Publishims-Yoshimaka.in. and (egroove ring) same recess\$: indentation output))	USTAT; US-EGFUB; EFT; SFC	2005,04 24 10.37
-	11	Fukushamu-Yoshimasa.un. and ((annul\$5) same refoss\$3))	USEAT; US-1GPUB; EED; JPC	2003 '04 '24 10:37
-	20107.	jgmone bing annul\$3  same recess\$€)	USEAT; US-EGPUE; ESI; JPC	2003 '04 '24 10.54
-	5422	and charines	UPEAT; UE-EGPUB; EED; JPC	2000,704 (24 10:39
	2104:	<pre>((dropte ring annul35) same recess\$3)) and (water substrate workplace)</pre>	USEAT; US-MGRUE; EFO; JPC	2002.704 2.24 10:39
-	6114	<pre>i) ur wire ring annui(3) same recess(3)) and (termer) and ((( groome ring annul\$3) same recess\$5)) and wafer substrat∈ workgr</pre>	USEAT; US-PGPUE; EES; SPS	2005/04/24 10:40
-	1537	.(. droove ring annul\$3) same reces(\$5)) and hammer) and ((( droove ring annul\$3) same recess\$5)) and wafer substrate works(************************************	CHEAT, US-IGPUB; EPD; JPC	.0000,704 124 10:45
-	2572	workging and claps:  (** our covering annu.\$3) same recess\$3)) and chamber) and (((groupe ring annul\$3)) came recess\$3)) and wafer substrate workgines () and vactum	USEAT; US-PGPUB; EP1; JF0	2003/04/24 10:40
-	848	( prove ring annul%) same recess(3)) and chammer) and (( prooffe ring annul%) same recess(5)) and wafer substrate work; (**d**))) and table and (((((groove ring annul%)) same recess(3)) and chamber) and ((groove ring annul%)) same recess(3)) and (wafer substrate work; (ede())) and vacuum)	USEAT; US-PGPUE; EPI, JPO	2003/64/24 10.40

- 13	<pre>(((((((groove ring annul\$3) same recess\$3)) and chamber) and ((((groove ring annul\$3) same recess\$3)) and (wifer substrate workpiece))) and table and ((((((groove ring annul\$)) same recess\$3)) and thamber and (((groove ring annul\$)) same recess\$3)) and (wafer substrate workpiece) and rabusm() and (table with (groove ring annus\$)</pre>	USPAF; US-PSPUB; EPD; JPO	2003/04/24 10:43
- 5	<pre>((f ( income ring annul()) same   reter()) and chamber) and ((((proove   ring annul()) same recess(3) and wafer   sigstrate wereplete()) and table and   ((( income ring annul()) same recess(3))   and chamber and (( income ring annul())   same recess(3)) and (wafer substrate   workplede) and valuum)( and (table with   recess())</pre>	USPAT; US-PGPUB; BPD: JPD	2603104724 13:43
- 3	<pre>2 ()(() gro we ring annul(3) same reter(3)) and thatmore and (()(groove ring annular) same resear(3) and wafer substrate wireplete)) and table and ()(()groove ring annul(3) same recess(3)) and (hamber and (()groove ring annul(3)) same resear(3)) and (wafer substrate workprese). and valuum): and (table with (grative ring annul(3)) and (((()groove ring annul(a)) same resear(b) and charmer) and (()grove ring annul(1)) same reter(())) and (wafer run trate workprese). and table) and (((()groove ring annul(a)) same resear(b)) and chamber) and ((()grove ring annul(b)) same reter(si))) and (wafer runstrate workprese). and valuum)) and (table with reter(()))</pre>	UBEAT; UBEPSPUE; EPT; JFD	2603.'04'24 10.43
- 70	2 ((gradue ring annul%3 (same redess%) and (lith graph, propolothography)	USEAT; US-PGPUE, EEG; JEI	2003.704, 24 10:55
	3 ()(incove ring annul\$3) same recess(3) and (linksgraphy photolothography)) and charger	USEAT; US-PGPUE; EFO; JFO	2003/04:24 10:55
- 17	7 (*(freque ring annul\$3) same recess\$3; and (lithography photolothography); and table	USEAT; US-PGPUE; EEC; JPC	2003, 04, 24 10:58
- 9	((() promise ring annull)) name recession and (lithography photolography) and chardner and (() prome ring annull) same secession and (lithography photolography hand talle)	USEAT; US-PGPUE, ESM; JEC	2005/04.24 11.01
- 3177	To becessif with (water substrate workplace)	USFAT; US-PGPUE, ESC; JEC	2005/04.24 11.02
- 715	<pre>() (recess\$3 with (uafer substrate     workpitche) and secess\$5 same (groome sing annul\$r)</pre>	USBAT; US PGPUB, EEC, JEC	2003/04/24 11:03
- 715	<pre>(reness33 with (wafer sub trate      vorug(e) and (recess\$) with (wafer      sub-trate wirepiece) and (recess\$) came      (grouve ring annul\$)</pre>	USEAT; US-PGPUE, EPO; JPC	2001/04,24 11:03
- 180	<pre>[ [(redeads) with wafer substrate   workprede; and (recess) with [wafer   substrate workpiede) and (recess) dame</pre>	USEAT; US-PGPUE; EPC; JPC	2005/04,24 11 04
- 118	<pre>(groove ring annul\$3)  )) and chamber ((recess\$3 with 'wafer substrate workpice)) and (recess\$5 with 'wafer substrate workpiece)) and (recess\$3 same (groove ring annul\$3)) )) and table</pre>	USFAT; US-PGPUE, EPO; JPO	2003/04/24 11:04

-		(((recess\$3 with (wafer substrate workpiece) and ((recess\$3 with (wafer substrate workpiece)) and (recess\$3 same (growthe ring annul\$3))) and chamber) and ((recess\$5 with (wafer substrate workpiece)) and (recess\$3 with wafer substrate workpiece)) and recess\$3 same (growthe ring annul\$1))) and table)	USPAT; US-PGPUB, EPU; JPI	2003/04/24 11.04
-	6-7	workpress and ((recess\$3 with wafer substrate workpress) and ((recess\$3 with wafer substrate workpress (and recess\$1 same (greece ring annul())) and chamber) and ((recess\$8 with (wafer substrate workpress)) and ((recess\$3 with wafer substrate workpress() and recess\$3 same (greece ring annul())) and table)) and lithograph\$2	USPAR; US PSPCE; EF; JF1	2003/04/24 11:29
-	21780	(visuan evacuat)3) with (ring annul\$3)	UHPAT, UH PSPUB, EPP; JEH	2003/04/24 11:35
-	450	((ne-lam eracquat\$3) with (ring smul\$3)) same raple	USTAT; UT-PGPUB, EP:; JEI	2003/04/24 11:36
-		((vacuum evacuat\$3) with (ring annul\$3)) same recess\$3	USFAT; US-PGPUB; EBW; JEI	0003/04/34 11:36
-		<pre>((:resplain evacuat\$3) with reing annul\$3)) same tabler and ( vacuum erabuat\$3) with (rise annul\$5) same recess\$3;</pre>	USEAT, US-PGPUE; EF; JEI	.003,04,334 11:37
-	-	73 Westrolas	USTAT, US PGPUE, EBY; JEI	: 003,04,::4 12:39
-		73 6r3.pcls. and table	USTAT, US-PGPCE, EPD; JEI	1003,04,24 12:30
-		73 Mm . pols. and (groove armul\$) recess\$3)	USFAT; US-PSPUE; ED:; JEI	. 003/04/24 12:34
-		43: J. Dols. and table	UNEAT, UNEAT, EP (; JEC	1003,704,84 18:50
-		(413 locals, and table ) and ((vacuum evatut93) same (ring annul;3 grove))	USPAT; US-PGPUB; EPO; UFC	2003/04/24 12:51
-		((438)%.cols. and table ) and ( macuum evaph(03) same (ring annul(3 grouve))) and table	USPAT; US-PGPUB; EP:; JEI	1003,'04,'24 12:51
-		([435 ].crls. and table ) and ("macuum errock!]) same (ring annul(3 gradue))) and recess?	UUTAT; U- PGPUE; EE ; JEI	003/04/24 12:51 003/04/24 12:53
_	12.	([4:% \$.bdls. and table ) and vacuum evacut([) same (ring annul(3 grouve))) and table and ((438/\$.dcls. and table ) and ((vacuum evacut(3)) same (ring annul(3 grouve))) and recess(3)	EF , JF1	, 003, 04, 1.4 1 33
-	446149	(hitadhi cannon).as.	USEAT; US-PGPUE; ED ; JEG	003/04/24 12:53
-	19566	((hita.hi dannon).as.) and chamber	USEAT; UE-PGPUS; ES , JEI	; 000/04/24 12:53
-		(( hirathi cannon).as.) and thamber) and (table with (grocve annulus ring))	UEPAT; UE-PGPUE; EPC; JPC	.003/04/24 18:54
-	0	lithegraphy same table same groove same relects	USPAT, US-PGPUE, EPO; JPO	2003/04/24 13.21